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APPLICATION NO. FILING DATE FIRST NAMED INVENTOR ATTORNEY DOCKET NO. CONFIRMATION NO. 09/895,511 06/29/2001 042390P11354 Ted Liang 8234 7590 EXAMINER 12/15/2004 Michael A. Bernadicou ZERVIGON, RUDY BLAKELY, SOKOLOFF, TAYLOR & ZAFMAN LLP ART UNIT Seventh Floor PAPER NUMBER 12400 Wilshire Boulevard 1763

DATE MAILED: 12/15/2004

Please find below and/or attached an Office communication concerning this application or proceeding.

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	Application No.	Applicant(s)	47
Office Action Summary	09/895,511	LIANG ET AL.	
	Examiner	Art Unit	
	Rudy Zervigon	1763	
The MAILING DATE of this communication app Period for Reply	pears on the cover sheet with the o	correspondence address	
A SHORTENED STATUTORY PERIOD FOR REPL THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.1 after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a repl - If NO period for reply is specified above, the maximum statutory period - Failure to reply within the set or extended period for reply will, by statute Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however, may a reply be tiry within the statutory minimum of thirty (30) day will apply and will expire SIX (6) MONTHS from a cause the application to become ABANDONE	mely filed /s will be considered timely. If the mailing date of this communication (D) (35 U.S.C. § 133).	n.
Status			
 Responsive to communication(s) filed on <u>27 S</u> This action is FINAL. 2b) This Since this application is in condition for alloward closed in accordance with the practice under E 	s action is non-final. nce except for formal matters, pro		3
Disposition of Claims			
 4) Claim(s) 1,4-12 and 18-33 is/are pending in the 4a) Of the above claim(s) is/are withdraws 5) Claim(s) is/are allowed. 6) Claim(s) 1,4-12 and 18-33 is/are rejected. 7) Claim(s) is/are objected to. 8) Claim(s) are subject to restriction and/or 	wn from consideration.		
Application Papers			
9) The specification is objected to by the Examine 10) The drawing(s) filed on is/are: a) acc		Examiner.	
Applicant may not request that any objection to the	•		
Replacement drawing sheet(s) including the correct		•	d).
Priority under 35 U.S.C. § 119			
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority document: 2. Certified copies of the priority document: 3. Copies of the certified copies of the priority document: application from the International Bureau * See the attached detailed Office action for a list	s have been received. s have been received in Applicati rity documents have been receive u (PCT Rule 17.2(a)).	on No ed in this National Stage	
Attachment(s)			
Notice of References Cited (PTO-892) Notice of Draftsperson's Patent Drawing Review (PTO-948) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date	4) Interview Summary Paper No(s)/Mail Da 5) Notice of Informal P 6) Other:		

Application/Control Number: 09/895,511

Art Unit: 1763

DETAILED ACTION

Page 2

Claim Rejections - 35 USC § 103

1. The text of those sections of Title 35, U.S. Code not included in this action can be found in a prior Office action.

2. Claims 1, 4-12, 18, 20, 25, and 27-31 are rejected under 35 U.S.C. 103(a) as being unpatentable over Casey, Jr. et al (USPat. 6,042,738) as demonstrated by Baum, Aaron Wolf et al (US 5,684,360 A) in view of Hashimoto, Hiroyuki (US 6,420,701 B1).

Casey teaches an apparatus (Figure 1) including:

- i. A holder (26) to mount a substrate / mask (30) in a chamber (22) by a stage (24) Regarding the particular identity of the article to be processed, it is well established that apparatus claims must be structurally distinguished from the prior art (In re Danley, 120 USPQ 528, 531 (CCPA 1959). "Apparatus claims cover what a device is, not what a device does ."(emphasis in original) Hewlett Packard Co . v. Bausch & Lomb Inc ., 15 USPQ2d 1525, 1528 (Fed. Cir. 1990), MPEP 2114). Further, a claim containing a "recitation with respect to the manner in which a claimed apparatus is intended to be employed does not differentiate the claimed apparatus from a prior art apparatus" if the prior art apparatus teaches all the structural limitations of the claim. Exparte Masham, 2 USPQ2d 1647 (Bd. Pat. App. & Inter. 1987).
- ii. A stage (24) adapted to position the holder in a chamber (22), and adapted to move in different directions (column 4, line 64 column 5, line 3)
- iii. A pumping system ("vacuum chamber 22"; column 4, lines 31) adapted to evacuate the chamber

- iv. A first electron column¹ (28; Figure 1; column 3, lines 8-16, "image and mill the workpiece"; column 4, lines 5-10; column 5, lines 5-10) imaging system (54; column 4, lines 38-45; column 5, lines 5-10) adapted to locate (column 6, lines 17-30) an opaque defect (abstract; column 1, lines 5-10; column 2, lines 28-50; column 8, line 62 column 9, line 2;) in the substrate / mask
- v. A gas delivery system (45, 34; column 5, lines 22-38) adapted to dispense a reactant gas towards the defect
- vi. A second electron column¹ delivery system (32; column 4, line 64 column 5, line 12) adapted to direct electrons towards the opaque defect (column 3, lines 60-65) to induce chemical etching by the reactant gas, and said electrons to induce said gas to etch said opaque defect without ion "bombardment, and without ion implantation or knock-on of atoms" "methods of gas-assisted etching using an etching gas including bromine" (abstract). It is noted that when the structure recited in the reference is substantially identical to that of the claims, claimed properties or functions are presumed to be inherent (In re Best, 562 F.2d 1252, 1255, 195 USPQ 430, 433 (CCPA 1977); MPEP 2112.01).
- vii. DUV/EUV mask / substrate (column 1, lines 35-45)
- viii. Chrome opaque defect (column 3, lines 3-4; line 55)
- ix. An ion focusing control system (18; column 4, lines 28-44) and scanning control system (62, column 4, lines 39-43)
- x. An acceleration system ("JEOL Model 6400") providing a low acceleration voltage (column 9, lines 20-25)

¹ Baum, Aaron Wolf et al (US 5,684,360 A) teaches the art-accepted definition of "electron beam column" (column

- xi. A computer controller (50, column 4, lines 38-45; column 7, lines 33-44) adapted to control the electron delivery system
- xii. The gas delivery system (34; column 5, lines 22-38) is also adapted to "dispense a carrier gas towards said opaque defect", "said gas comprises water or oxygen" (claim 29), "said gas comprises Xenon Fluoride (XeF2)" (claim 30) Applicant's claim 18, 29, 30 limitations are intended use claim requirements. Further, it has been held that claim language that simply specifies an intended use or field of use for the invention generally will not limit the scope of a claim (Walter, 618 F.2d at 769, 205 USPQ at 409; MPEP 2106). Additionally, in apparatus claims, intended use must result in a structural difference between the claimed invention and the prior art in order to patentably distinguish the claimed invention from the prior art. If the prior art structure is capable of performing the intended use, then it meets the claim (In re Casey,152 USPQ 235 (CCPA 1967); In re Otto, 136 USPQ 458, 459 (CCPA 1963); MPEP2111.02).
- xiii. Applicant's claim 20 limitation of "the reactant gas absorbs to said opaque defect and becomes disassociated" are intended use claim requirements. Further, it has been held that claim language that simply specifies an intended use or field of use for the invention generally will not limit the scope of a claim (Walter, 618 F.2d at 769, 205 USPQ at 409; MPEP 2106). Additionally, in apparatus claims, intended use must result in a structural difference between the claimed invention and the prior art in order to patentably distinguish the claimed invention from the prior art. If the prior art structure is capable of

performing the intended use, then it meets the claim (In re Casey,152 USPQ 235 (CCPA 1967); In re Otto, 136 USPQ 458, 459 (CCPA 1963); MPEP2111.02).

Casey does not teach that Casey's first electron column (28; Figure 1; column 3, lines 8-16, "image and mill the workpiece"; column 4, lines 5-10; column 5, lines 5-10) is used to direct a first set of electrons towards a substrate.

Hashimoto teaches an electron column (12; Figure 6; column 11, lines 58-67) used to direct a first set of electrons towards a substrate (15; Figure 6).

It would have been obvious to one of ordinary skill in the art at the time the invention was made to add Hashimoto's electron column to Casey's apparatus.

Motivation to add Hashimoto's electron column to Casey's apparatus is for locating and processing specific regions of the substrate as taught by Hashimoto (column 7, lines 1-10). Further, it is well established that the duplication of parts is obvious (In re Harza, 274 F.2d 669, 124 USPQ 378 (CCPA 1960) MPEP 2144.04).

3. Claim 19 is rejected under 35 U.S.C. 103(a) as being unpatentable over Casey, Jr. et al (USPat. 6,042,738) as demonstrated by Baum, Aaron Wolf et al (US 5,684,360 A) in view of Hashimoto, Hiroyuki (US 6,420,701 B1) and Fuji, Eiji et al (US 5,876,504 A). Casey and Hashimoto are discussed above. Casey and Hashimoto are do not teach the angle of gas injection of Casey's gas delivery system (45, 34; column 5, lines 22-38) has an angular dispersion of 5-25°. Fuji teaches a variably positioned gas injection nozzle (8; Figure 2).

It would have been obvious to one of ordinary skill in the art at the time the invention was made to replace Casey and Hashimoto's gas injector nozzle with Fuji's variably positioned gas injection nozzle (8; Figure 2).

Art Unit: 1763

Motivation to replace Casey and Hashimoto's gas injector nozzle with Fuji's variably positioned gas injection nozzle (8; Figure 2) is for establishing laminar flow on the substrate as taught by Fuji (column 4, lines 35-40).

4. Claims 21-24, 26, 32, and 33 are rejected under 35 U.S.C. 103(a) as being unpatentable over Casey, Jr. et al (USPat. 6,042,738) as demonstrated by Baum, Aaron Wolf et al (US 5,684,360 A) in view of Hashimoto, Hiroyuki (US 6,420,701 B1). Casey and Hashimoto are discussed above. Casey does not teach operating pressures in 0.5-10.0mTorr, "a beam comprising a current of about 0.05-1.0nA", second electrons beams with diameters of about 5-125nm and energies of 0.-3.0keV. Casey further does not teach that his reactor is either reaction-limited or mass transfer limited as claimed by Applicant's claim 33 – However, when the structure recited in the reference is substantially identical to that of the claims, claimed properties or functions are presumed to be inherent (In re Best, 562 F.2d 1252, 1255, 195 USPQ 430, 433 (CCPA 1977); MPEP 2112.01).

Hashimoto further teaches an electron beam apparatus (Figure 7) including operating pressures up to 100picoTorr (column 6, lines 15-20), beam currents of about 1.0nA (column 7, lines 1-10), electrons beams with diameters of about 5-125nm ("not more than 1 micrometer"; column 7, lines 1-10) and energies of 3.0keV (column 7, lines 23-31).

It would have been obvious to one of ordinary skill in the art at the time the invention was made to replace Casey's electron emitting column with Hashimoto's electron emitting column (12; Figure 7).

Motivation to replace Casey's electron emitting column with Hashimoto's electron emitting column (12; Figure 7) is for thin film processing as taught by Hashimoto (column 6, lines 30-41).

Response to Arguments

5. Applicant's arguments with respect to claims 1, 4-12, 18-24 have been considered but are moot in view of the new grounds of rejection.

Conclusion

6. Applicant's amendment necessitated the new grounds of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

7. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Examiner Rudy Zervigon whose telephone number is (571) 272.1442. The examiner can normally be reached on a Monday through Thursday schedule from 8am through 7pm. The official fax phone number for the 1763 art unit is (703) 872-9306. Any Inquiry of a general nature or relating to the status of this application or proceeding should be directed to the Chemical and Materials Engineering art unit receptionist at (571) 272-1700. If the

Application/Control Number: 09/895,511

Art Unit: 1763

examiner can not be reached please contact the examiner's supervisor, Gregory L. Mills, at (571)

272-1439.

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Page 8